

WEST Search History

DATE: Saturday, May 01, 2004

Hide?	<u>Set Name</u>	<u>Query</u>	<u>Hit Count</u>
	<i>DB=USPT; PLUR=YES; OP=ADJ</i>		
<input type="checkbox"/>	L34	etch\$3 and 6369887.pn.	1
<input type="checkbox"/>	L33	resist and 6369887.pn.	1
<input type="checkbox"/>	L32	l15 and 6369887.pn.	0
<input type="checkbox"/>	L31	resist and 5940175.pn.	0
<input type="checkbox"/>	L30	l15 and 5940175.pn.	0
<input type="checkbox"/>	L29	resist and 6015718.pn.	0
<input type="checkbox"/>	L28	l15 and 6015718.pn.	0
<input type="checkbox"/>	L27	etch\$3 and 5963315.pn.	0
<input type="checkbox"/>	L26	etching and 5963315.pn.	0
<input type="checkbox"/>	L25	l18 and 5963315.pn.	0
<input type="checkbox"/>	L24	l17 and L23	0
<input type="checkbox"/>	L23	l15 and 5963315.pn.	1
<input type="checkbox"/>	L22	l15 and 6660528.pn.	0
<input type="checkbox"/>	L21	('6699399' '6136211')!.PN.	2
<input type="checkbox"/>	L20	L19 and l17	59
<input type="checkbox"/>	L19	l14 and l15 and l16 and l18	67
<input type="checkbox"/>	L18	etching chamber or etching machine	2596
<input type="checkbox"/>	L17	silicon oxide or silicon nitride or silicon oxynitride or polysilicon	101976
<input type="checkbox"/>	L16	wafer	116440
<input type="checkbox"/>	L15	photoresist	60050
<input type="checkbox"/>	L14	(count\$3 or measur\$3) with (particulate or particle or (dynamic particle))	43015
	<i>DB=EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ</i>		
<input type="checkbox"/>	L13	l1 and l2 and l12	1
<input type="checkbox"/>	L12	etching chamber or etching machine	2522
<input type="checkbox"/>	L11	L10 and l4	1
<input type="checkbox"/>	L10	l9 and l2 and l3	9
<input type="checkbox"/>	L9	(monitor\$3 or indicat\$3 or determin\$6) with (contamination or pollut\$3 or particle)	16954
	<i>DB=PGPB; PLUR=YES; OP=ADJ</i>		
<input type="checkbox"/>	L8	US-20030073247-A1.did.	1

<input type="checkbox"/>	L7	US-20030073247-A1.did.	1
		<i>DB=EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L6	l4 and L5	1
<input type="checkbox"/>	L5	l1 and l2 and l3	13
<input type="checkbox"/>	L4	silicon oxide or silicon nitride or silicon oxynitride or polysilicon	92208
<input type="checkbox"/>	L3	wafer	185662
<input type="checkbox"/>	L2	photoresist	51059
<input type="checkbox"/>	L1	(count\$3 or measur\$3) with (particulate or particle or (dynamic particle))	20963

END OF SEARCH HISTORY